

鉛フリー低リンタイプ無電解ニッケル/PTFE複合めっき液
Lead-free and Low Phosphorus Type Electroless Nickel/PTFE Composite Plating Process

トップニコジットLPFE

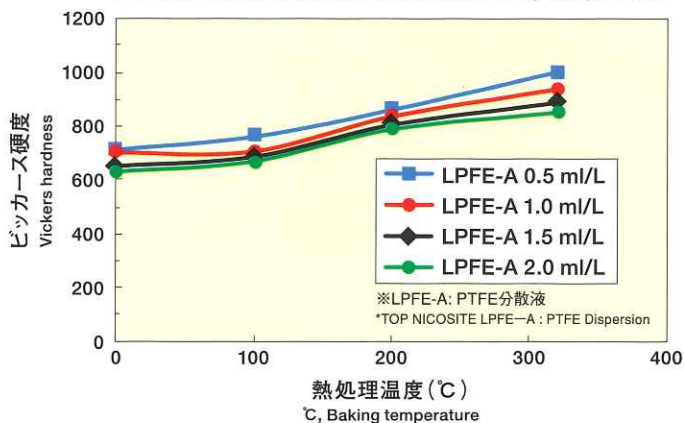
TOP NICOSITE LPFE

- 析出皮膜は硬度が高く、摺動性に優れる
- リン含有率が1~3wt.%と低く、PTFE共析量も約10vol.%以下で硬度が高い
- 析出皮膜は、通常Hv600以上の硬度が得られ、320℃の熱処理により約Hv1000の硬度が得られる
- High hardness and excellent sliding property
- Phosphorus content is 1 to 3 wt.% and co-deposited volume of PTFE is approximately 10 vol.% or less, so that hardness of the deposited film is high
- Hardness of the deposited film is normally 600 Hv or more, and it will be approximately 1,000 Hv after baking at 320 °C

性能 Performance

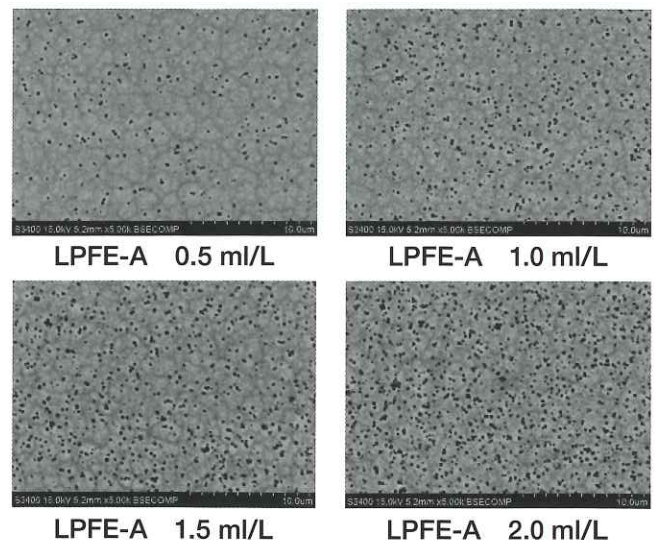
熱処理温度と皮膜硬度の関係

Relation between film hardness and baking temperature



めっき皮膜の表面SEM写真

SEM images of surfaces of plating films



低リン無電解ニッケル皮膜およびトップニコジットLPFE皮膜の摩擦係数

Coefficient of friction of low phosphorus type electroless nickel plating film and plating film by TOP NICOSITE LPFE

